SILICON PROCESSING FOR THE VLSI ERA

VOLUME 1:

PROCESS TECHNOLOGY

STANLEY WOLF Ph.D.

Professor, Department of Electrical Engineering
California State University, Long Beach
Long Beach, California
and
Instructor, Engineering Extension, University of California, Irvine

RICHARD N. TAUBER Ph.D.

Manager of VLSI Fabrication
TRW - Microelectronics Center
Redondo Beach, California
and
Instructor, Engineering Extension, University of California, Irvine

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